

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Lee Cheng on April 25, 2008.

2. The application has been amended as follows:

In line 2 of claim 27, before "electrode plates", inserted --parallel--;

In line 10 of claim 27, after "spaces", inserted --, wherein each of the corresponding through holes in said electrode plates and insulating member are coaxial, and wherein said electrode plates are embedded in said insulating member.--.

3. Claims 3 and 25-26 are cancelled.

Information Disclosure Statement

4. The information disclosure statement (IDS) submitted on June 11, 2008 was filed after the mailing date of the Notice of Allowance on May 2, 2008. The submission is in compliance with the provisions of 37 CFR 1.97. Accordingly, the information disclosure statement is being considered by the examiner.

Allowable Subject Matter

5. Claims 2, 4-5, 7-17, 19-22, 27, and 29 are allowed.

REASONS FOR ALLOWANCE

6. The following is an examiner's statement of reasons for allowance:

The prior art, either singly or in combinations, fails to anticipate or render obvious a plasma treatment apparatus comprising: a pair of parallel electrode plates having a plurality of through holes; an insulating member having a plurality of through holes, which is disposed between the electrode plates such that positions of the through holes of the electrode plates correspond to the positions of file through holes of the insulating member; a gas supply means configured to supply a plasma generation gas into a plurality of discharge spaces formed by the through holes of the electrode plates and the through holes of the insulating member; and voltage applying means configured to apply a voltage between the electrode plates to generate plasmas of the plasma generation gas simultaneously in the discharge spaces, wherein each of the corresponding through holes in the electrode plates and insulating member are coaxial, and wherein the electrode plates are embedded in the insulating member.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Crowell whose telephone number is (571) 272-1432. The examiner can normally be reached on M-Th (9:30 -6:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system.~ Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000

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